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Analysis of Metallic Impurities in Si Wafers Using Fully Automated VPD-ICP-MS

Introduction

Analysis of Metallic Impurities in Si Wafers Using Fully Automated VPD-ICP-MS

This work demonstrates the coupling of an IAS Expert_PS VPD (vapor phase decomposition) system with the Perkinelmer NexION® 5000 ICP-MS, delivering a fully automated, reliable solution for the determination of metallic impurities introduced during Si wafer production, thanks to the ICP-MS' sensitivity and ability to remove spectral inferences when performing trace analysis in combination with a platform that eliminates manual operation and chemical exposure to operators to prevent Si wafer contamination.

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